

FTW



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

: **Confirmation No. 1862**

Taku HIRAYAMA et al.

: Attorney Docket No. 2005_0892A

Serial No. 10/537,290

: Group Art Unit 1795

Filed June 1, 2005

: Examiner Sin J. Lee

CHEMICAL-AMPLIFICATION TYPE
SILICONE-BASED POSITIVE-WORKING
PHOTORESIST COMPOSITION

: **Mail Stop: AMENDMENT**

RESPONSE

THE COMMISSIONER IS AUTHORIZED
TO CHARGE ANY DEFICIENCY IN THE
FEES FOR THIS PAPER TO DEPOSIT
ACCOUNT NO 23-0975

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Official Action dated May 16, 2008, please amend the present application as follows: